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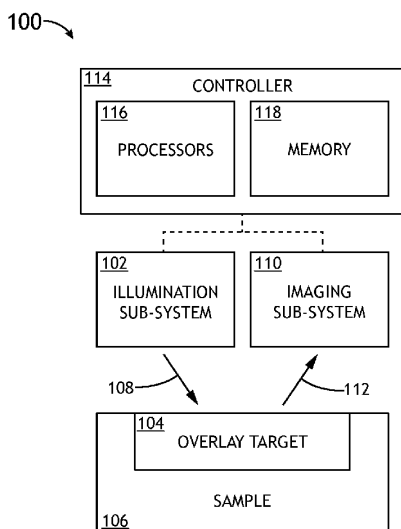
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(54) Title: OVERLAY MARK DESIGN ENABLING LARGE OVERLAY MEASUREMENT



(57) Abstract: An overlay metrology system may receive images of an overlay target on a sample, where the overlay target includes Moiré structures in which first-layer features and second-layer features partially overlap, where overlap regions include regions of overlap between the first-layer and second-layer features, where non-overlap regions include regions of non-overlap between the first-layer and second-layer features. The system may further, determine a coarse overlay measurement based at least in part on the one or more non-overlap regions of the one or more images, determine a fine overlay measurement based at least in part on the one or more overlap regions of the one or more images, and generate an output overlay measurement based on the coarse overlay measurement and the fine overlay measurement.

FIG.1A